

WHAT IS CLAIMED IS:

1. An electron-beam drawing apparatus for drawing a desired pattern by applying an electron beam formed by using a plurality of apertures onto the surface of a sample, comprising a first quadrangular aperture in which two opposite sides are parallel with each other and each corner forms a right angle, a second parallelogrammatic aperture in which two opposite sides are parallel with each other, and deflection means for an electron beam passing through the second aperture, wherein a desired pattern is drawn on the surface of a sample.

2. The electron-beam drawing apparatus according to claim 1, wherein the second parallelogrammatic aperture has a diagonal width of 1 μ m or less and a longitudinal width which can be changed depending on the first aperture.

3. The electron-beam drawing apparatus according to claim 1, wherein oblique-side-portion-contour decomposition means for cutting out an oblique-side portion of a drawn shape at a predetermined width adjusted to an aperture shape is included to draw the cut-out oblique-side portion by using the parallelogrammatic aperture.

4. The electron-beam drawing apparatus according to

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